Claims

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- 1. A plasma generation system comprising a high voltage generator (20) connected to at least two electrodes (26, 28), one having a large radius of curvature while the other has a small radius of curvature, characterized in that said high voltage generator is controlled in such a way as to maintain constant the average frequency of occurrence of current discharges from the at least one electrode with a small radius of curvature (26) to the at least one electrode with a large radius of curvature (28).
- 2. The plasma generation system as claimed in claim 1, characterized in that said electrode with a large radius of curvature has a plane geometry.
- 3. The plasma generation system as claimed in claim 1 or claim 2, characterized in that it additionally comprises a dielectric insulator (30) inserted between the electrodes and in that said high voltage generator is a sinusoidal or pulsed alternating generator (20).
- 4. The plasma generation system as claimed in claim 3, characterized in that said high voltage generator comprises a high gain transformer (40) driven by a transistor (42) operating in switching mode under the control of a low voltage signal generator (46) having a specified fixed frequency and a variable mark-space ratio.
- 5. The plasma generation system as claimed in claim 1, characterized in that it additionally comprises a resistance (48) connected between an earth potential and the at least one electrode with a large radius of curvature, to measure a voltage representing the current discharges from the at least one electrode with a small radius of curvature to the at least one electrode with a large radius of curvature.
 - 6. The plasma generation system as claimed in claim 1,

characterized in that it additionally comprises a current transformer (92) connected in the electrical circuit (22) supplying the electrodes, to measure a current representing the current discharges from the at least one electrode with a small radius of curvature to the at least one electrode with a large radius of curvature.

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- 7. The plasma generation system as claimed in claim 5 or 6, characterized in that it additionally comprises a high pass or band pass filter (50), so that only the part of said measured signal (74) representing the discharges occurring between the electrodes is recovered.
- 8. The plasma generation system as claimed in claim 7, characterized in that the measured and filtered signal (76) is converted by a conversion system (34), during a specified fixed period, into a specified continuous voltage (82) representing a mean number of electrical discharges.
- 9. The plasma generation system as claimed in claim 8, characterized in that said measured mean number of discharges is maintained by a control system (36) at a specified set value (38, 80) corresponding to said mean frequency of occurrence of the current discharges.
- 10. The plasma generation system as claimed in claim 3, characterized in that said high voltage generator comprises a high voltage chopper (98) distributing, alternately, a positive continuous high voltage and a negative continuous high voltage and a negative continuous of curvature (26) under the control of a low voltage signal generator (46) with a specified fixed frequency and a variable mark-space ratio.
- 35 11. The plasma generation system as claimed in claim 1 or claim 2, characterized in that the high voltage generator is a continuous generator.

12. The plasma generation system as claimed in claim 11, characterized in that said high voltage generator comprises a rectifier circuit (96) connected to the output of a high gain transformer (40) driven by a transistor (42) operating in switching mode under the control of a low voltage signal generator (46) having a specified fixed frequency and a variable mark-space ratio.

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13. A system for plasma sterilization in the presence of moisture, at atmospheric pressure and at ambient temperature, comprising a plasma generation system as claimed in any one of claims 1 to 12.